

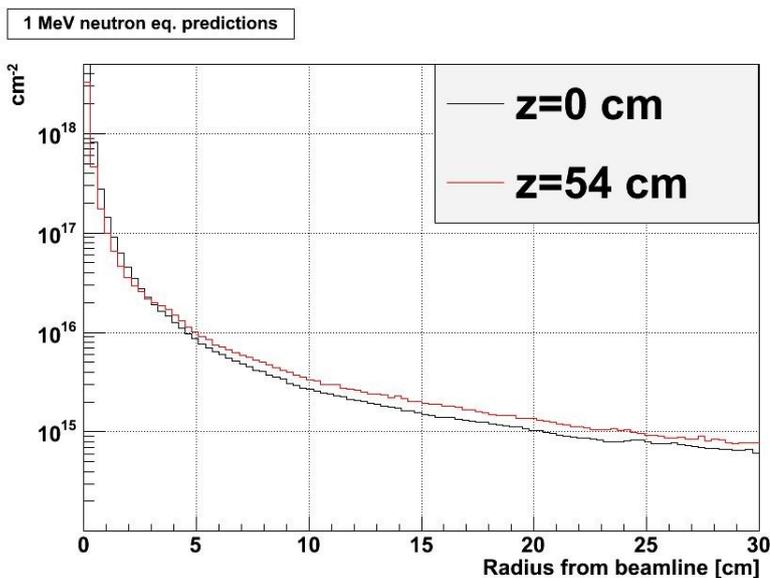
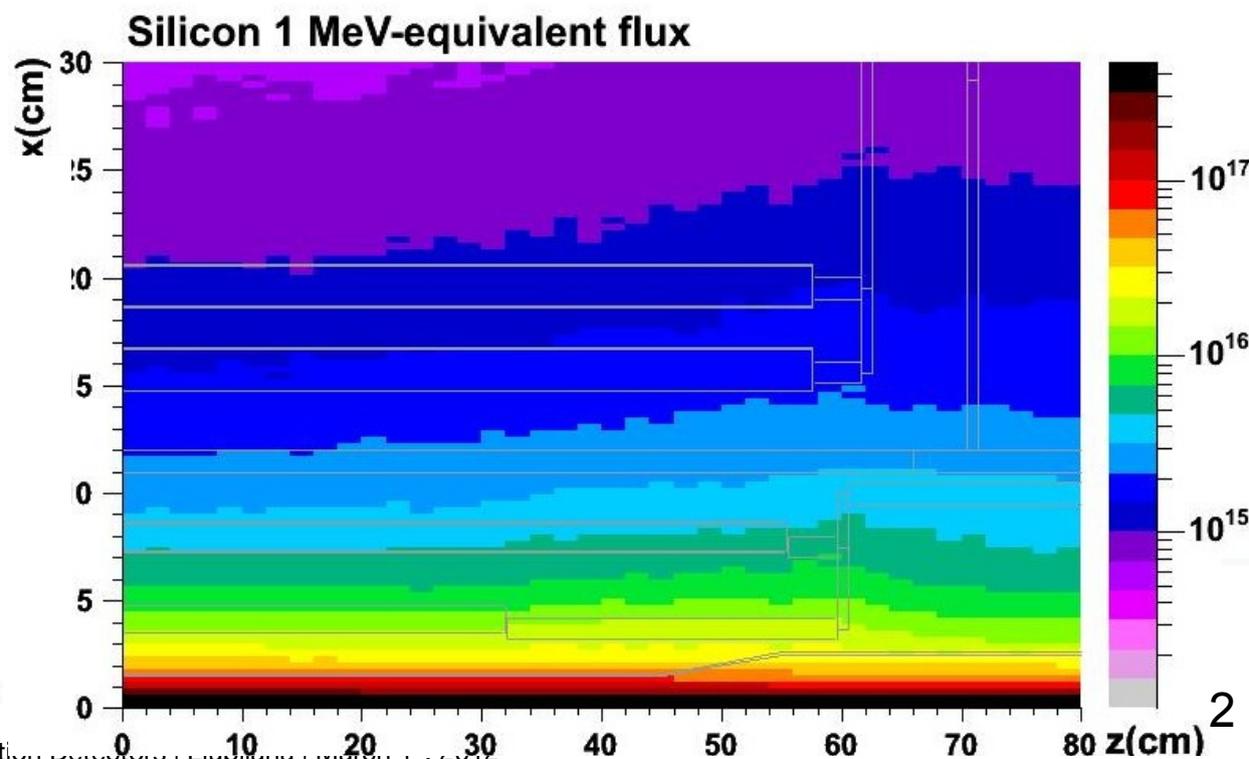
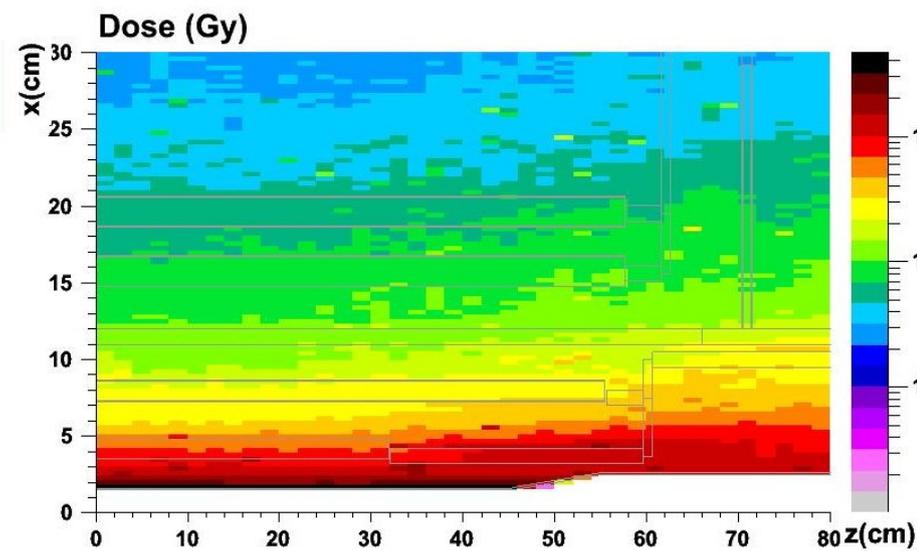
Radiation-hard active sensors in 180 nm HV CMOS technology

Daniel Muenstermann (CERN)

with lots of material from Ivan Peric (U Heidelberg)

Reminder: fluences at HL-LHC

- integrated luminosity: 3000 fb^{-1}
- including a safety factor of 2 to account for all uncertainties this yields for ATLAS:
 - at 5 cm radius:
 - $\sim 2 \cdot 10^{16} \text{ n}_{\text{eq}} \text{ cm}^{-2}$
 - $\sim 1500 \text{ MRad}$
 - at 25 cm radius
 - up to $10^{15} \text{ n}_{\text{eq}} \text{ cm}^{-2}$
 - $\sim 100 \text{ MRad}$
 - several m^2 of silicon



Implications

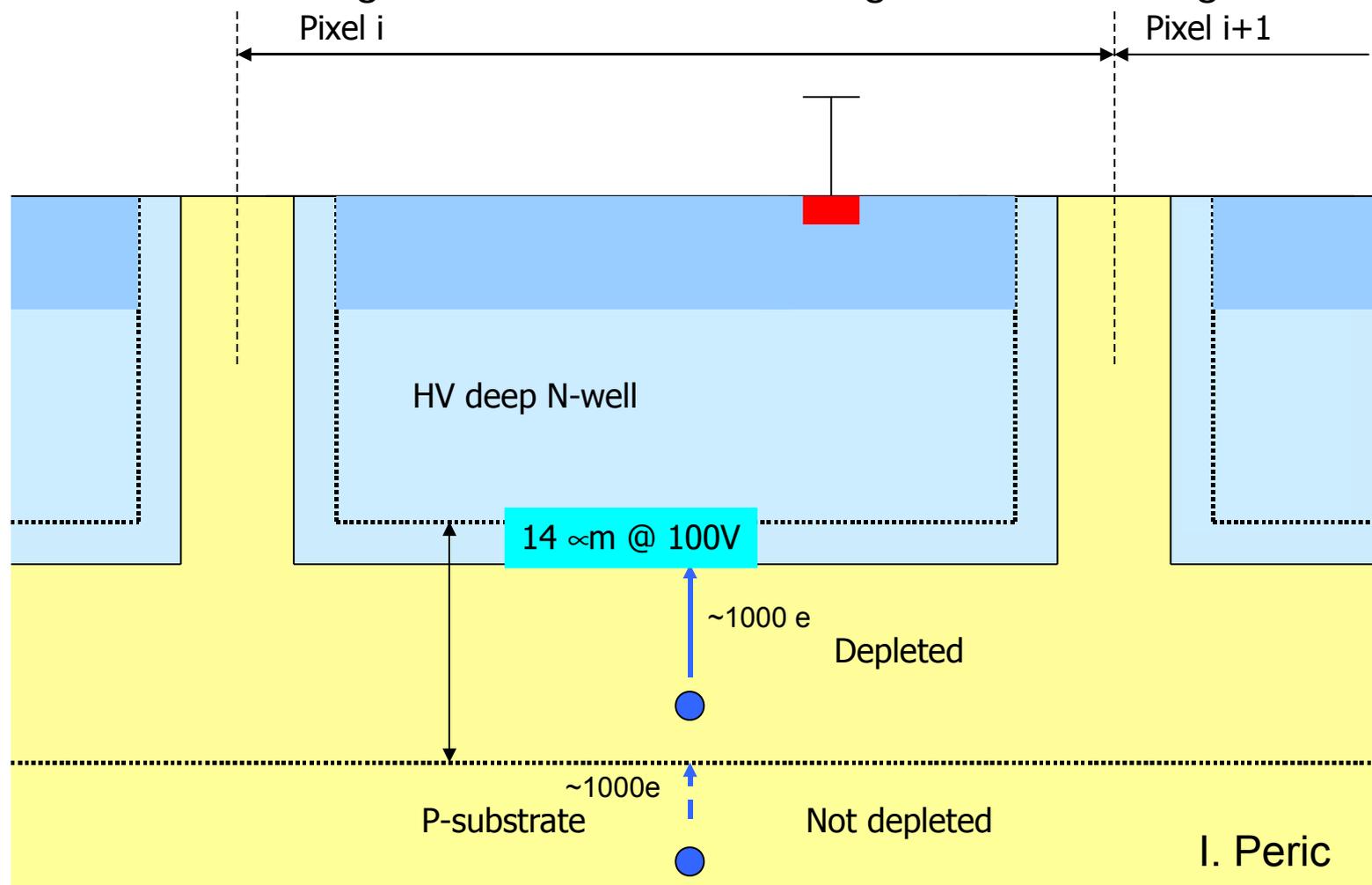
- High fluences: trapping dominant
 - reduce drift distance, increase field → reduce drift time:
 - 3D sensors
 - thin silicon
 - low depletion depth 'on purpose':
 - low(er) resistivity silicon
 - dedicated annealing to increase N_{eff}
- Large areas: low cost of prime importance
 - industrialised processes
 - large wafer sizes
 - cheap interconnection technologies
- Idea: explore industry standard CMOS processes as sensors
 - commercially available by variety of foundries
 - large volumes, more than one vendor possible
 - 8" to 12" wafers
 - low cost per area: "as cheap as chips"
 - (partially too) low resistivity p-type Cz silicon
 - thin active layer
 - wafer thinning possible

AMS H18 (and H35) HV-CMOS

- Project initiated and led by Ivan Peric (U Heidelberg)
- Austria Micro Systems offers HV-CMOS processes with 350 and 180 nm feature size, the latter one in cooperation with IBM
 - biasing of substrate to $\sim 100V$ possible
 - substrate resistivity $\sim 20 \text{ Ohm}\cdot\text{cm} \rightarrow N_{\text{eff}} > 10^{14}/\text{cm}^3$
 - radiation induced N_{eff} insignificant even for innermost layers
 - depletion depth in the order of 10-20 μm
 - on-sensor amplification possible - and necessary for good S/N
 - key: small pixel sizes \rightarrow low capacitance \rightarrow low noise
 - additional circuits possible, e.g. discriminator
 - beware of 'digital' crosstalk
 - full-sized radiation hard drift-based MAPS feasible, but challenging
 - aim for 'active sensors' in conjunction with rad-hard readout electronics first
- Scope of the talk:
 - Introduce the concept
 - Present first results with test chips
 - Details of a active sensor prototype currently being produced
 - Outlook: how small can pixels get?

A HV-CMOS sensor...

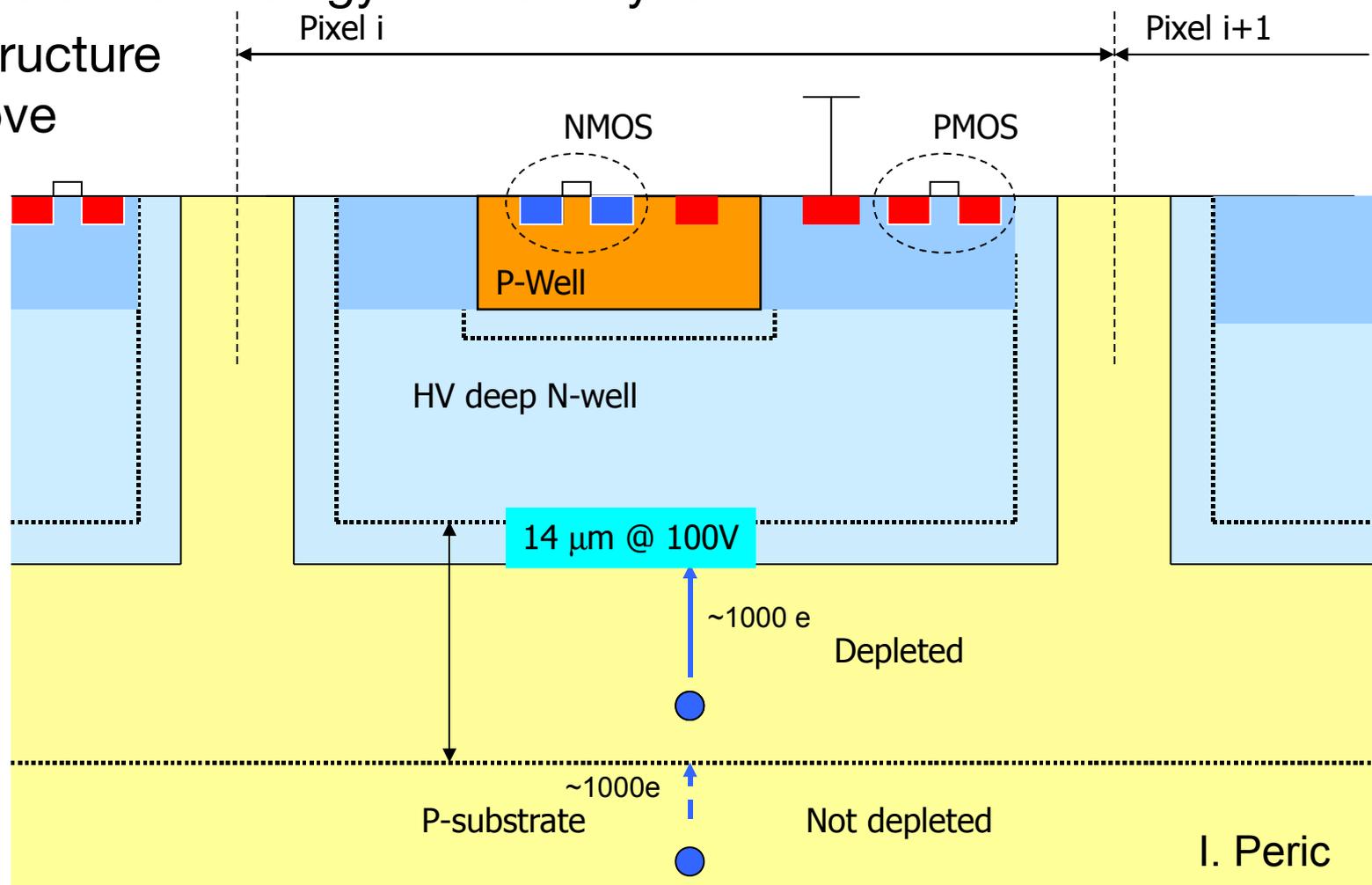
- essentially a standard n-in-p sensor
- depletion zone 10-20 μm : signal in the order of 1-2ke⁻
 - challenging for hybrid pixel readout electronics
 - new ATLAS ROC FE-I4 might be able to reach this region – but no margin



The depleted high-voltage diode used as sensor (n-well in p-substrate diode)

...including active circuits: *smart diode array (SDA)*

- implementation of
 - first amplifier stages
 - additional circuits: discriminators, impedance converters, logic, ...
- deep sub-micron technology intrinsically rad-hard
- triple-well structure would improve crosstalk-tolerance



CMOS electronics placed inside the diode (inside the n-well)

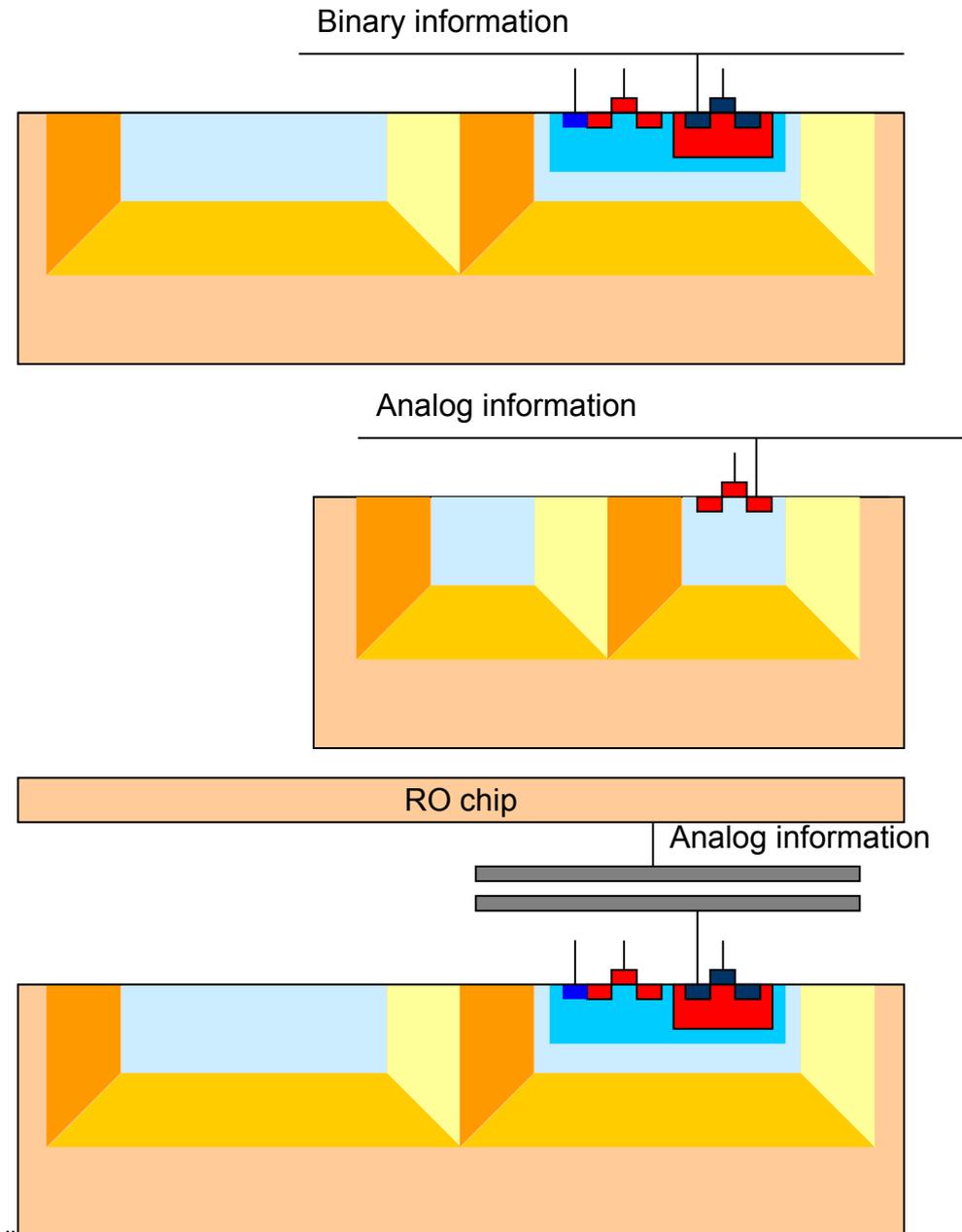
Prototypes

- Several test-chips submitted in both technologies already

SDA with sparse readout
("intelligent" CMOS pixels)
HV2/MuPixel chip

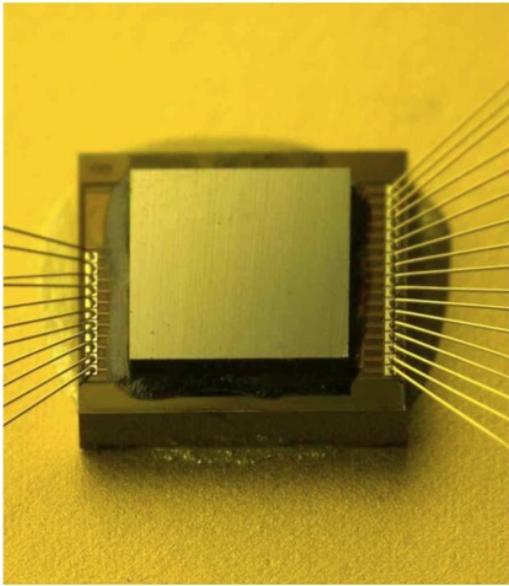
SDA with frame readout
(simple PMOS pixels)
HVM chip

SDA with capacitive readout
("intelligent" pixels)
Capacitive coupled pixel
detectors
CCPD1 and CCPD2 detectors



Prototype summaries

First chip – CMOS pixels
 Hit detection in pixels
 Binary RO
 Pixel size 55x55 μm
 Noise: 60e
 MIP seed pixel signal 1800 e
 Time resolution 200ns



Bumpless hybrid detector

CCPD1 Chip
 Bumpless hybrid detector
 Based on capacitive chip to chip
 signal transfer
 Pixel size 78x60 μm
 RO type: capacitive
 Noise: 80e
 MIP signal 1800e

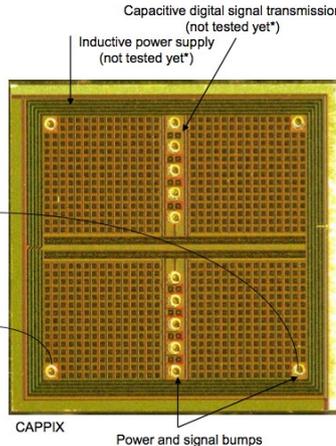
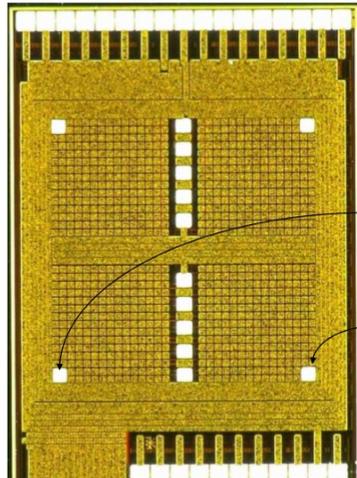
Frame readout - monolithic

PM1 Chip
 Pixel size 21x21 μm
 Frame mode readout
 4 PMOS pixel electronics
 128 on chip ADCs
 Noise: 90e
 Test-beam: MIP signal 2200e/1300e
 Efficiency > 85% (timing problem)
 Spatial resolution 7 μm
 Uniform detection

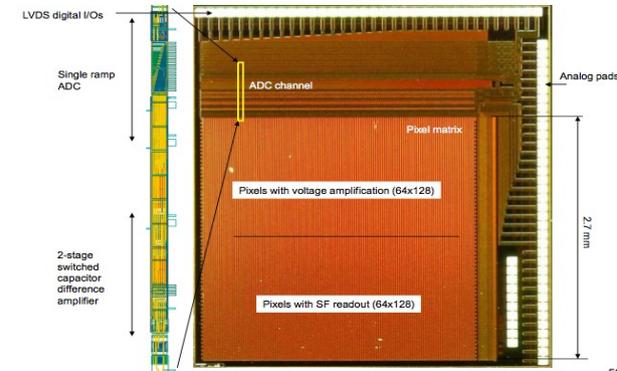
CCPD2 Chip
 Edgeless CCPD
 Pixel size 50x50 μm
 Noise: 30-40e
 Time resolution 300ns
SNR 45-60

PM2 Chip
 Noise: 21e (lab) - 44e (test beam)
Test beam: Detection efficiency 98%
Seed Pixel SNR ~ 27
Cluster Signal/Seed Pixel Noise ~ 47
Spatial resolution ~ 3.8 μm

Irradiations of test pixels
60MRad – SNR 22 at 10C (CCPD1)
 $10^{15} \text{n}_{\text{eq}}/\text{cm}^2$ – SNR 50 at 10C (CCPD2)

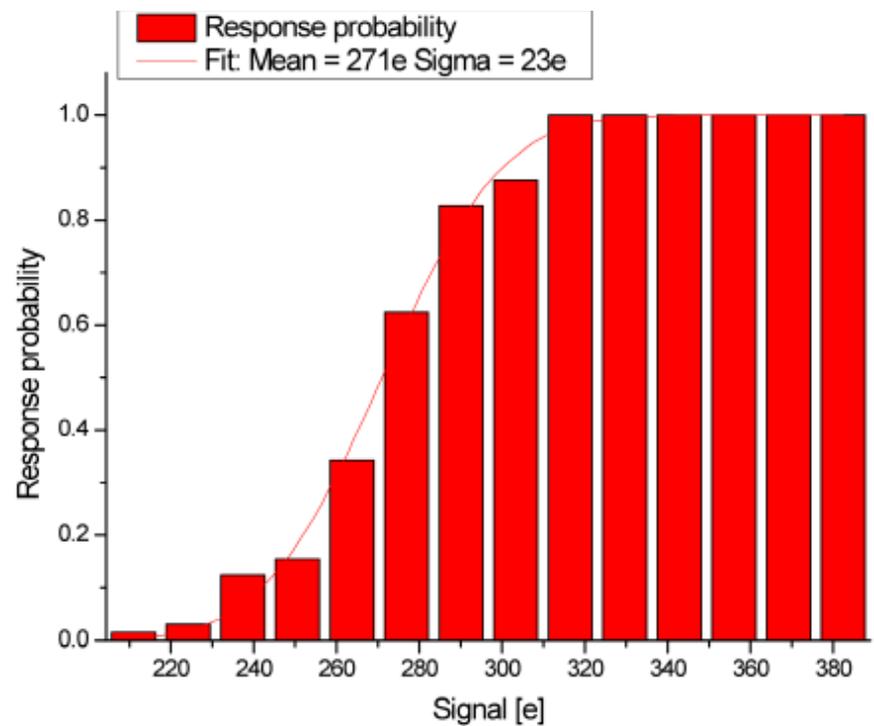
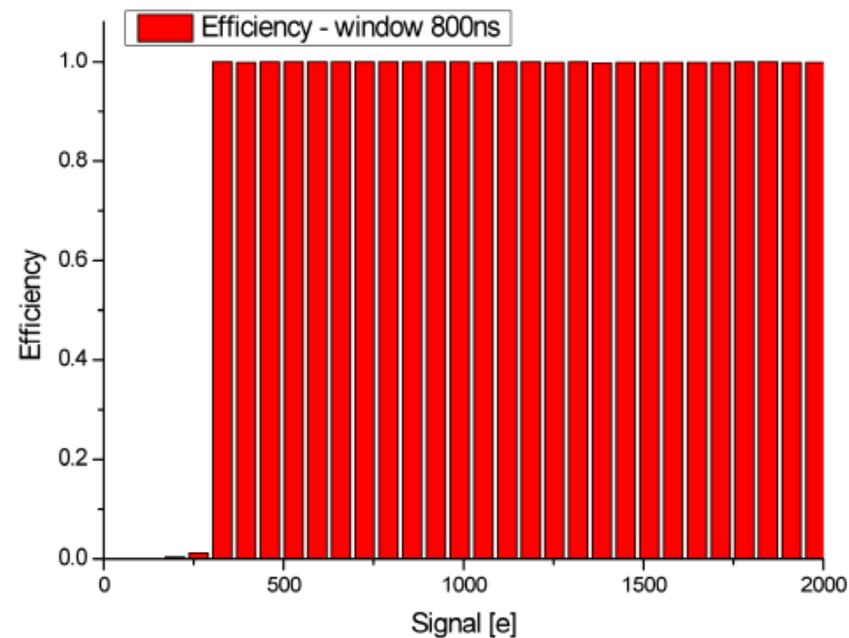


*If work, these features would allow to operate the readout chip without any mechanical contact



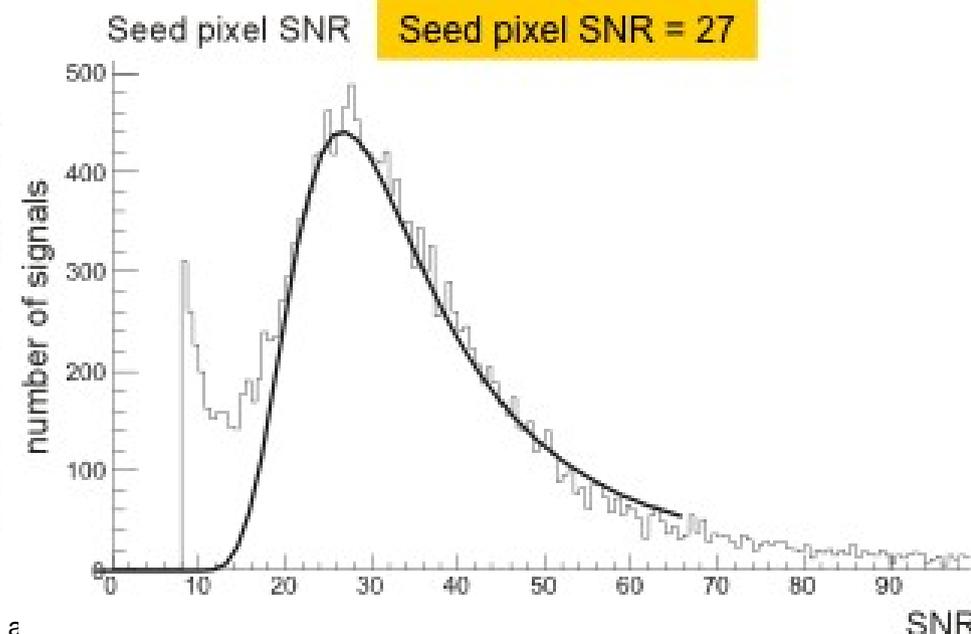
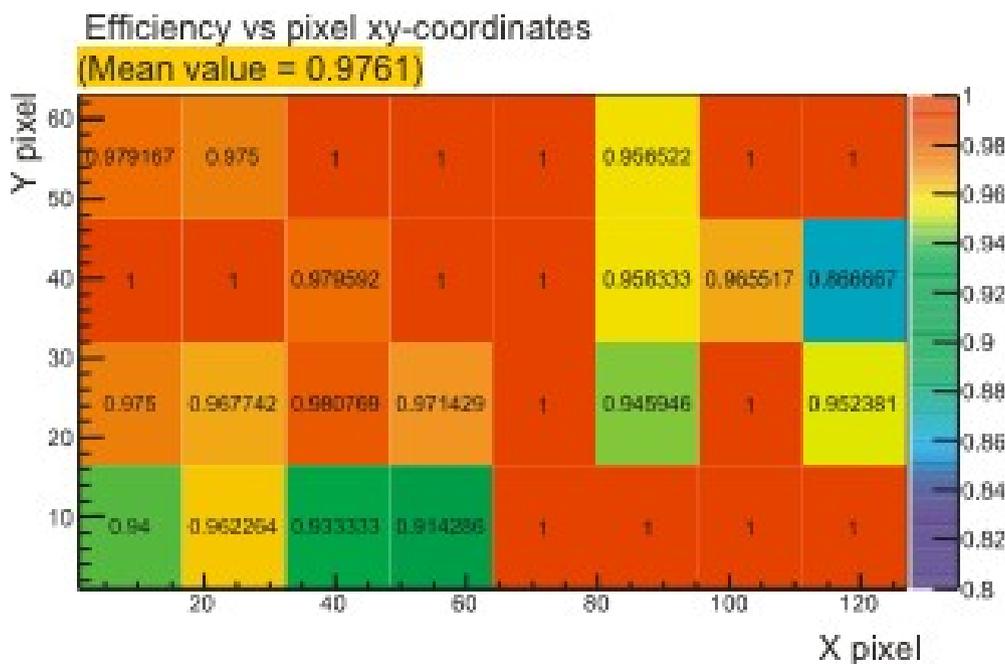
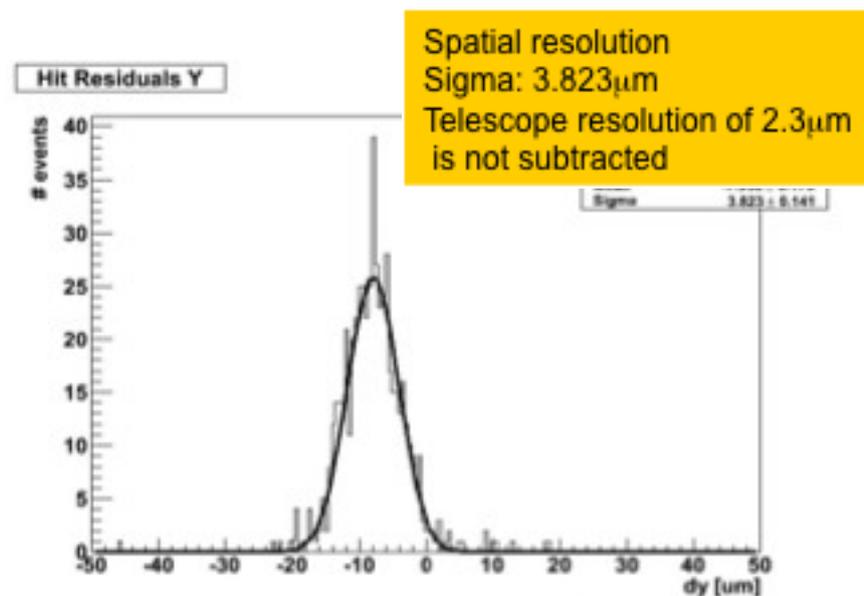
CCPD thresholds

- threshold set to about 300 electrons
- noise extracted from s-curve about 23 electrons (!)



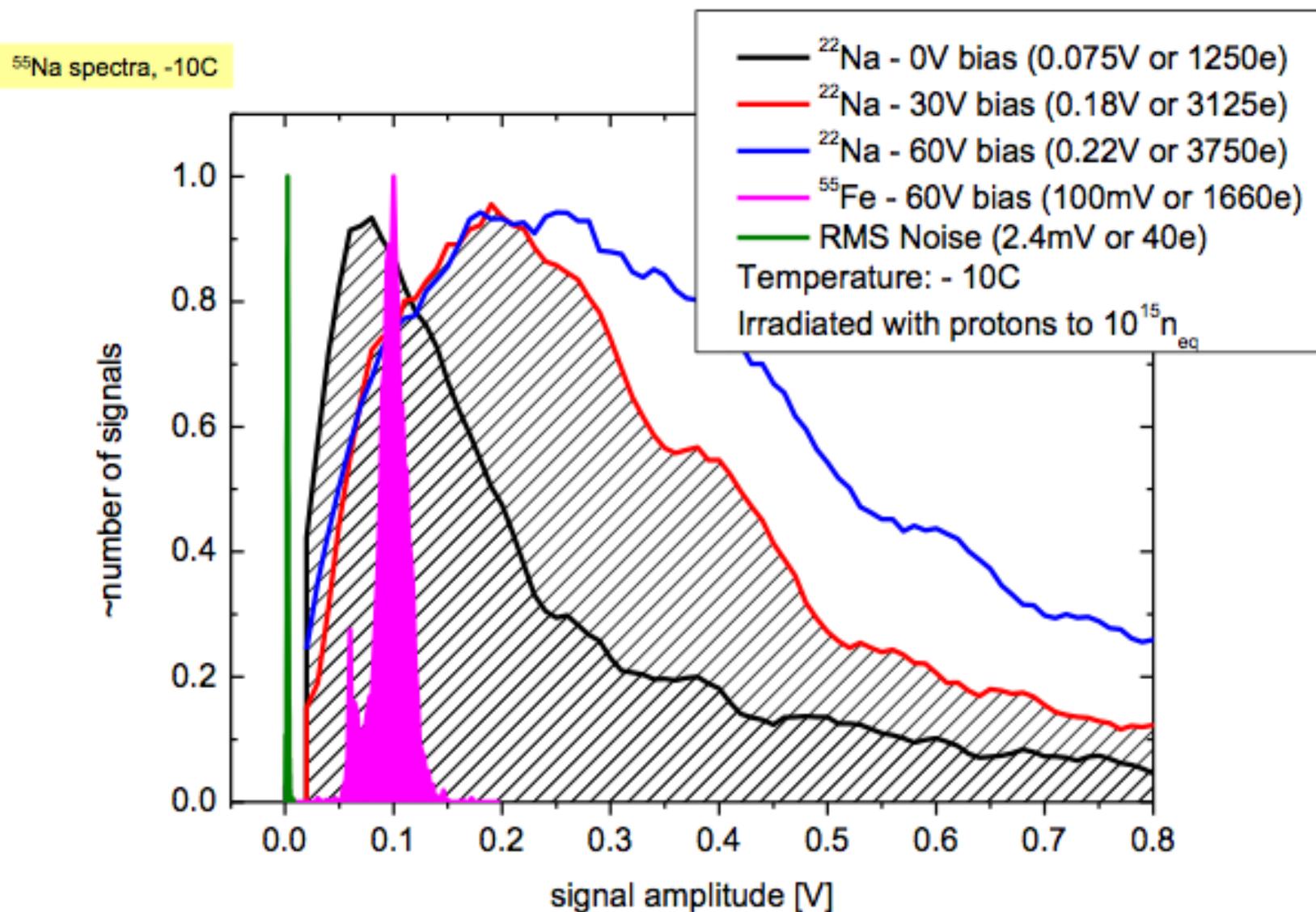
Test beam results

- excellent resolution
- very good S/N ratio
- efficiency limited by readout artifacts:
 - column-based readout
 - column not active during readout
 - data analysis did not correct for this
 - very small chip → low statistics



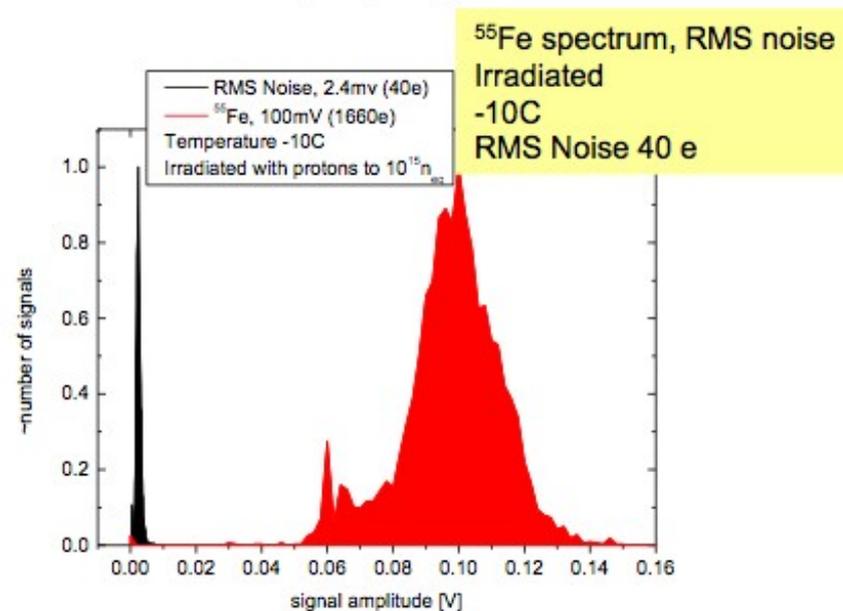
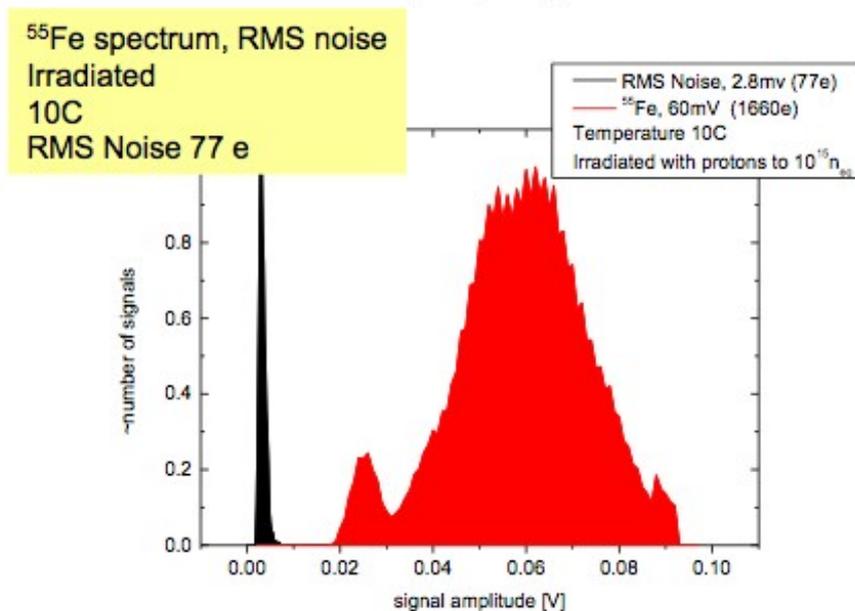
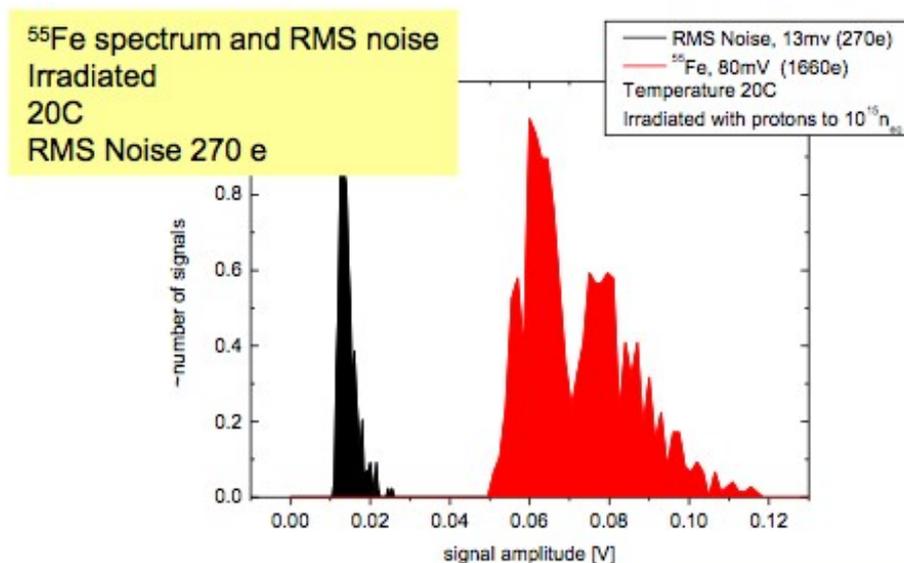
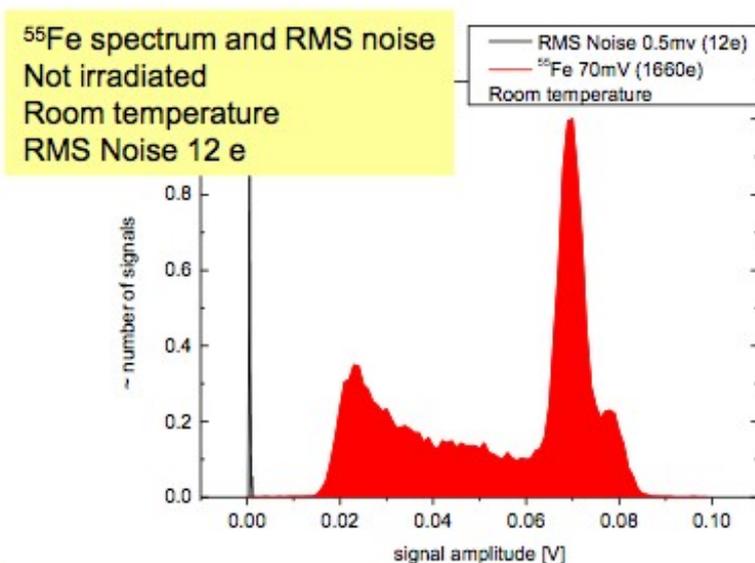
Some irradiated prototype results

- Irradiation with 23 MeV protons: 1×10^{15} neq/cm², 150MRad
- generally very good S/N ratio



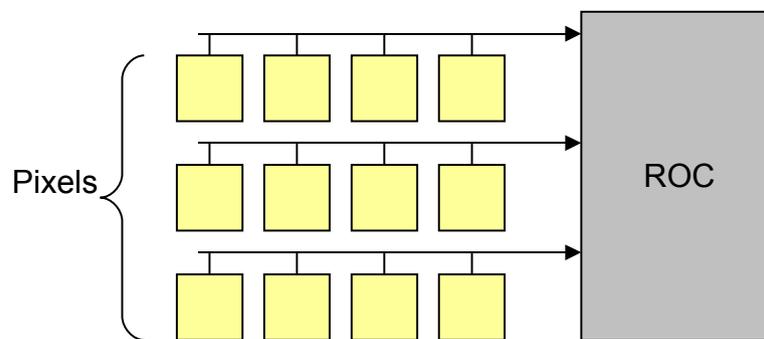
Some irradiated prototype results

- Irradiation with 23 MeV protons: 1×10^{15} neq/cm², 150MRad
- FE-55 performance recovers after slight cooling



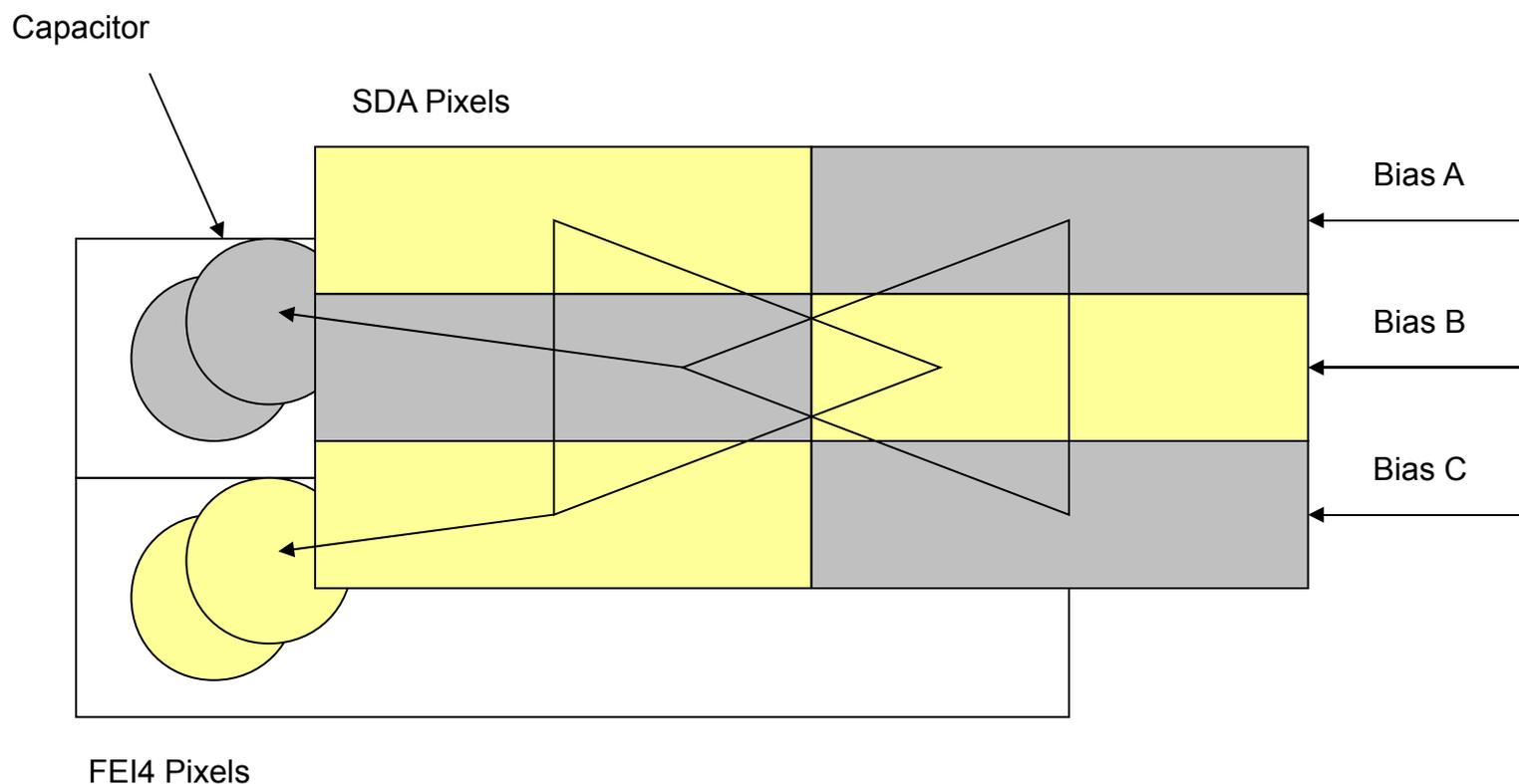
From MAPS to active sensors

- Existing prototypes would not be suitable for HL-LHC, mainly because
 - readout too slow
 - time resolution not compatible with 40 MHz operation
 - high-speed digital circuits might affect noise performance
- Idea: use HV-CMOS as sensor in combination with existing readout technology
 - fully transparent, can be easily compared to other sensors
 - can be combined with several readout chips
 - makes use of highly optimised readout circuits
 - can be seen as first step towards a sensor being integrated into a 3D-stacked readout chip (not only analogue circuits but also charge collection)
- Basic building blocks: *small* pixels (low capacitance, low noise)
 - can be connected in any conceivable way to match existing readout granularity, e.g.
 - (larger) pixels
 - strips



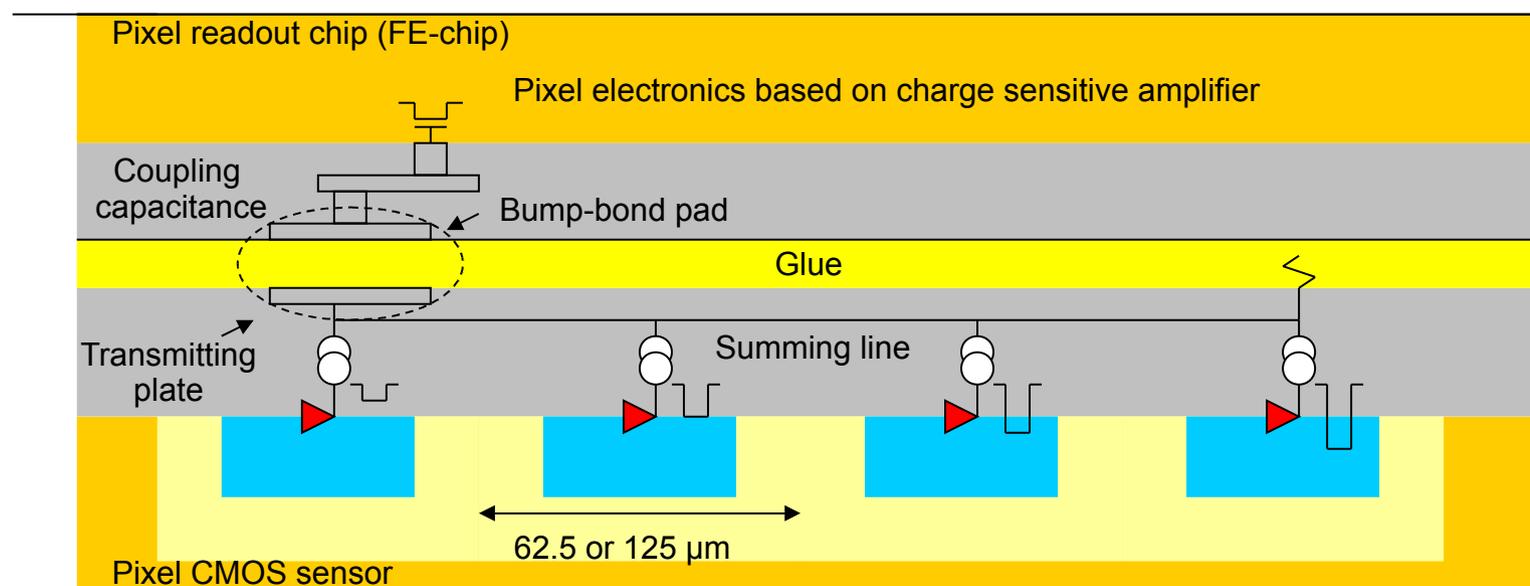
Pixels

- Possible/sensible pixel sizes: 20x20 to 50x125 μm
 - 50x250 μm (current ATLAS FE-I4 chip) too large
 - combine several sensor “sub-pixels” to one ROC-pixel
 - sub-Pixels encode their address/position into the signal as pulse-height-information instead of signal proportional to collected charge
 - routing on chip is well possible, also non-neighbour sub-pixels could be combined and more than one combination is possible



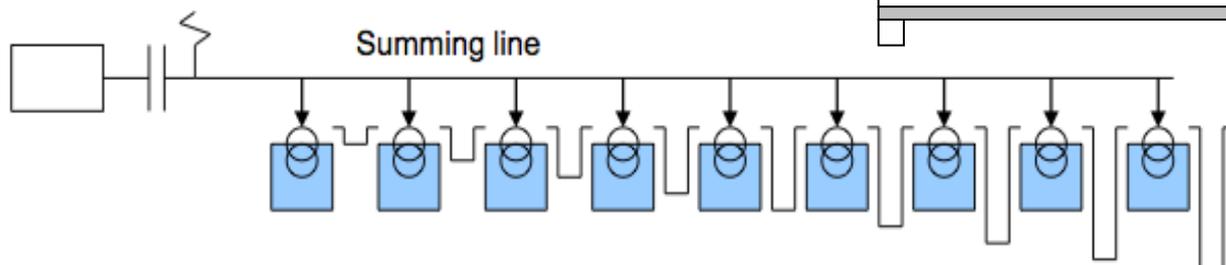
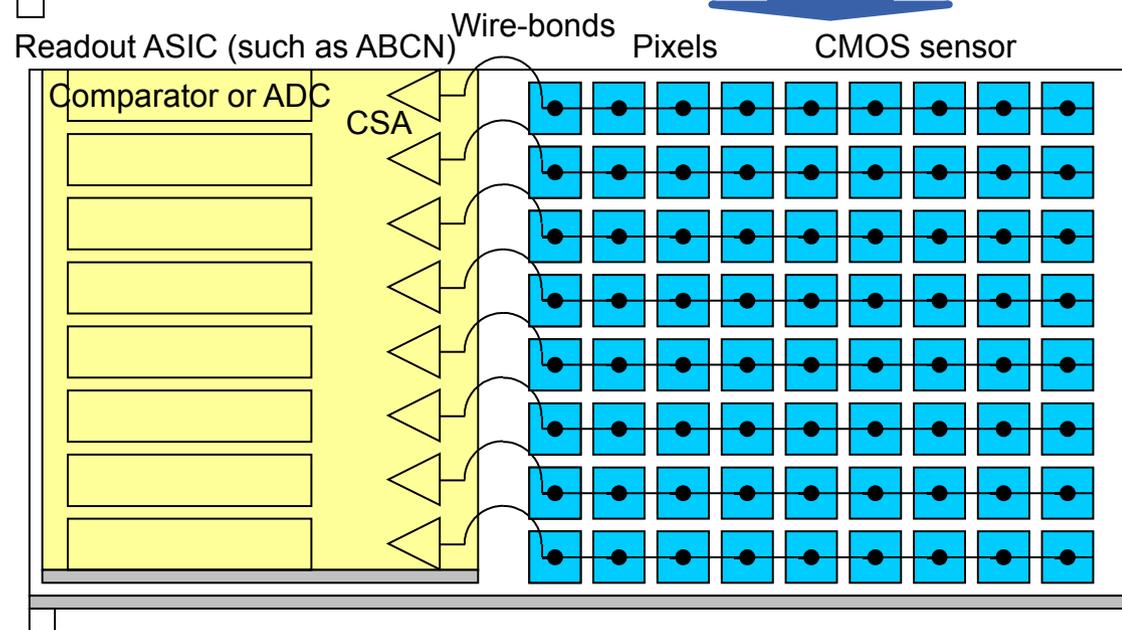
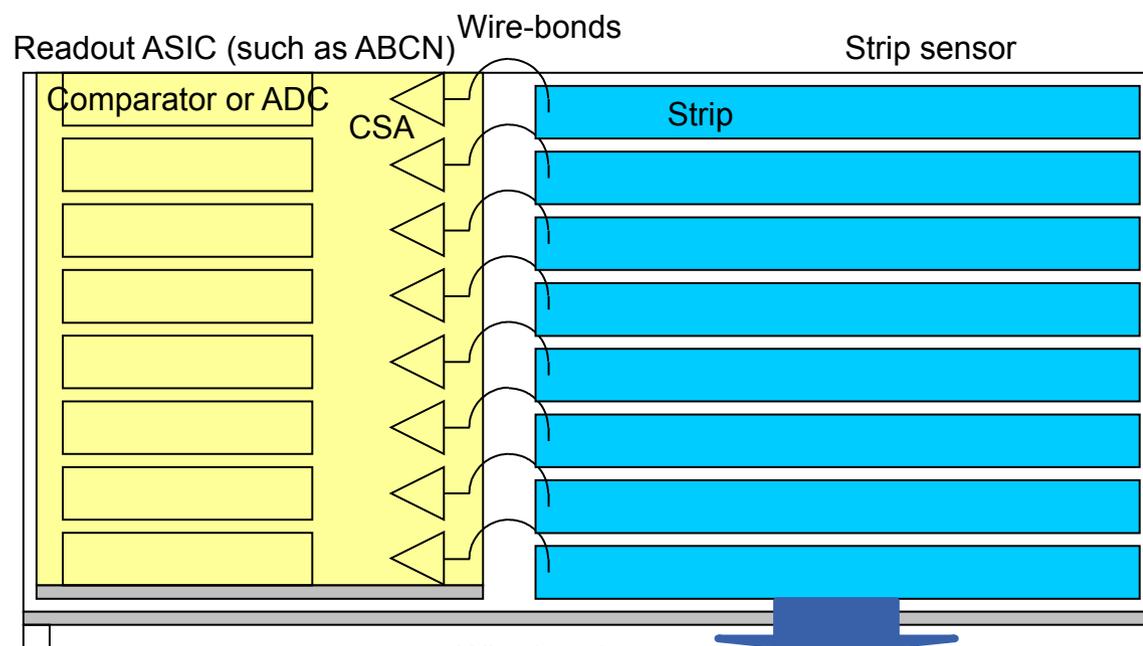
Pixels

- Possible/sensible pixel sizes: 20x20 to 50x125 μm
 - 50x250 μm (current ATLAS FE-I4 chip) too large
 - combine several sensor “sub-pixels” to one ROC-pixel
 - sub-Pixels encode their address/position into the signal as pulse-height-information instead of signal proportional to collected charge
 - routing on chip is well possible, also non-neighbour sub-pixels could be combined and more than one combination is possible
- Only reason not to use AC coupling with pixel sensors up to now was small coupling capacitance in association with low signal
 - amplification possible, hence AC transmission not a problem at all
 - would allow to get rid of costly bump-bonding



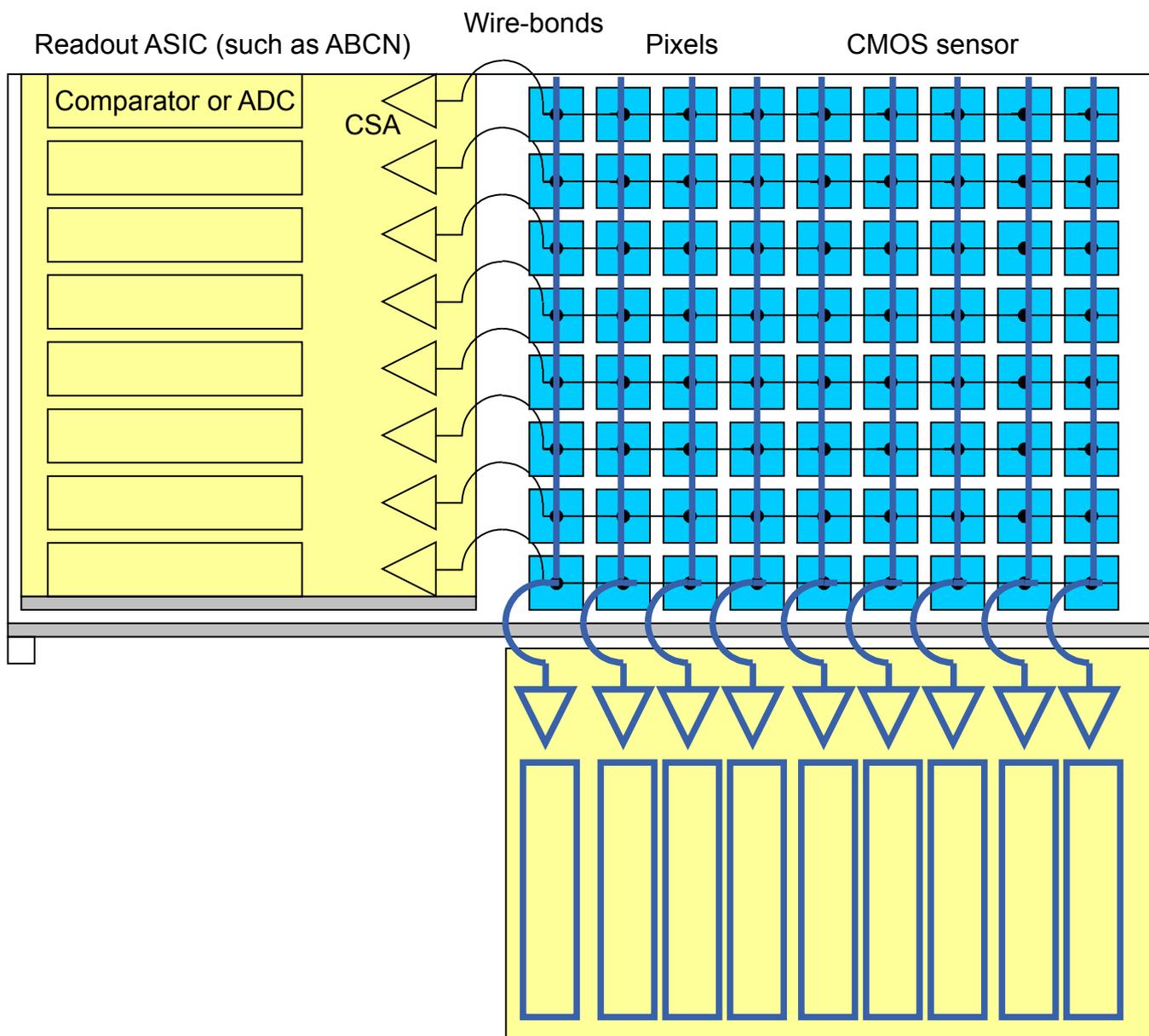
Strips

- Easiest idea would be to simply sum all pixels within a virtual strip
- Hit position along the strip could be again encoded by pulse height for analogue readout chips (e.g. Beetle)



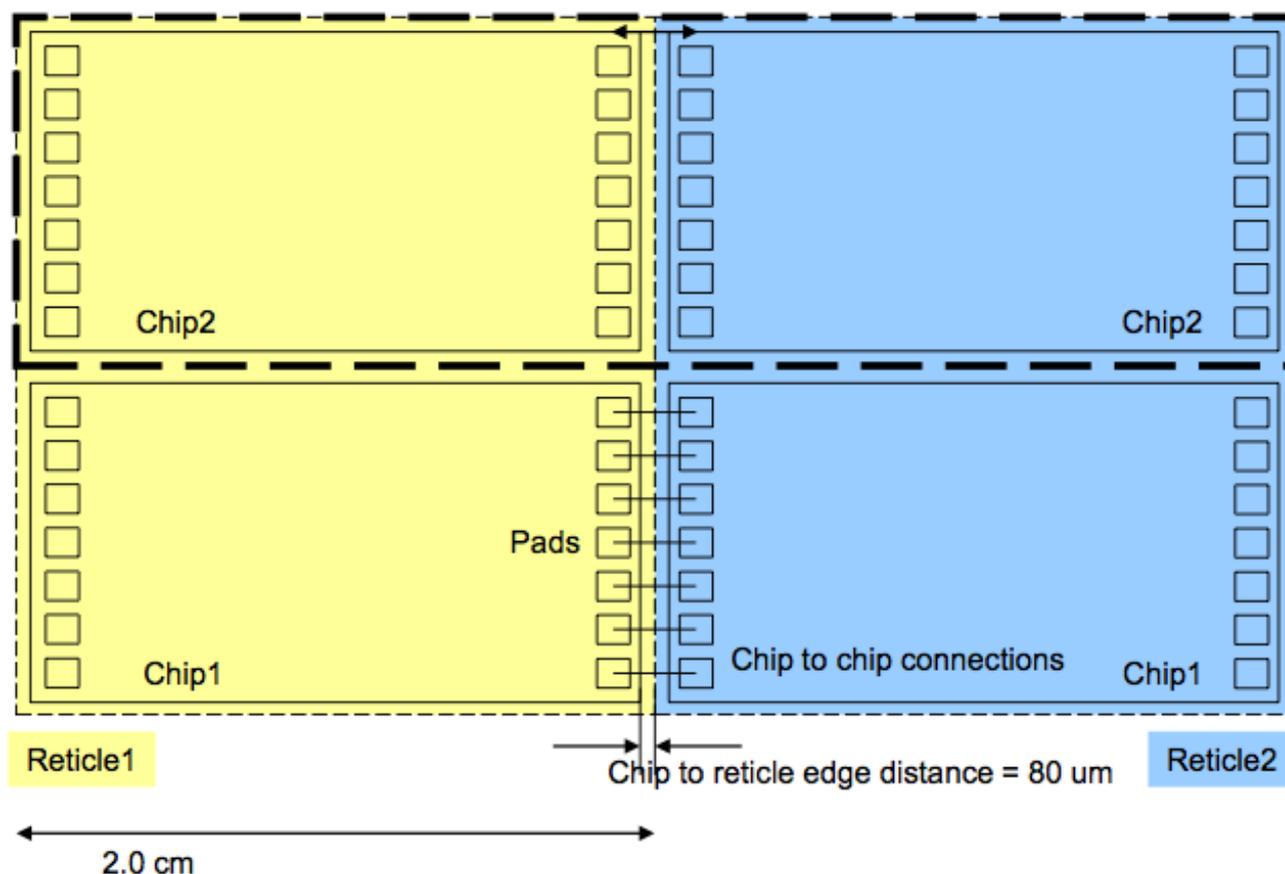
Strips

- Signals are digital so multiple connections are possible, e.g.
 - “crossed strips”
 - strips with double width but only half the pitch in r-phi



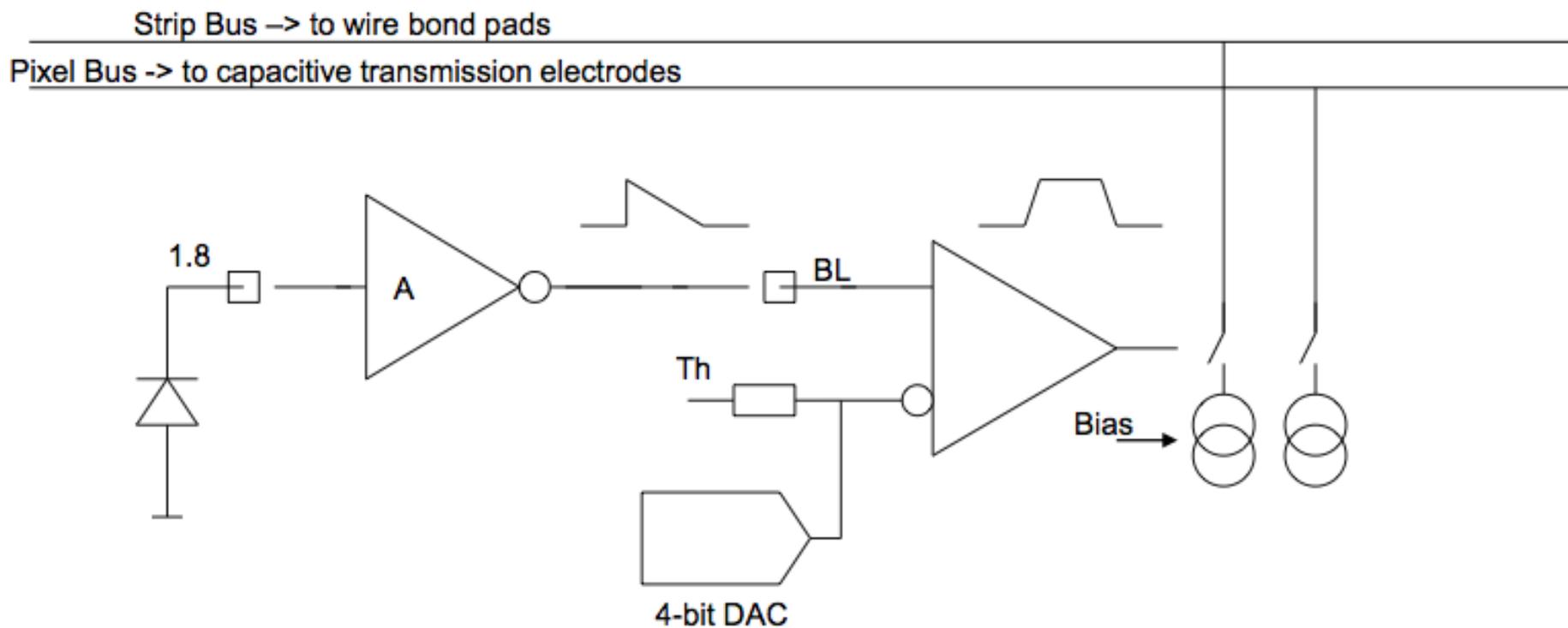
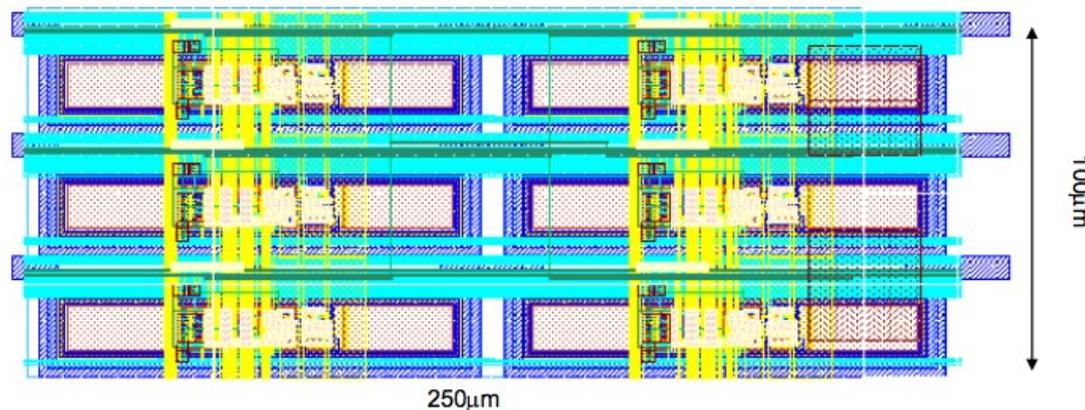
Reticule size/stitching

- Sensor size is currently limited by reticule size of $\sim 2 \times 2$ cm
 - however, the yield should be excellent (very simple circuit, essentially no “central” parts) so it might be interesting to cut large arrays of sensors from a wafer and connect individual reticules by
 - wire-bonding
 - post-processing (one metal layer, large feature size)
- There are HV-CMOS processes/foundries which allow for stitching
- Very slim dicing streets
 - Gaps between 1-chip modules could be rather narrow



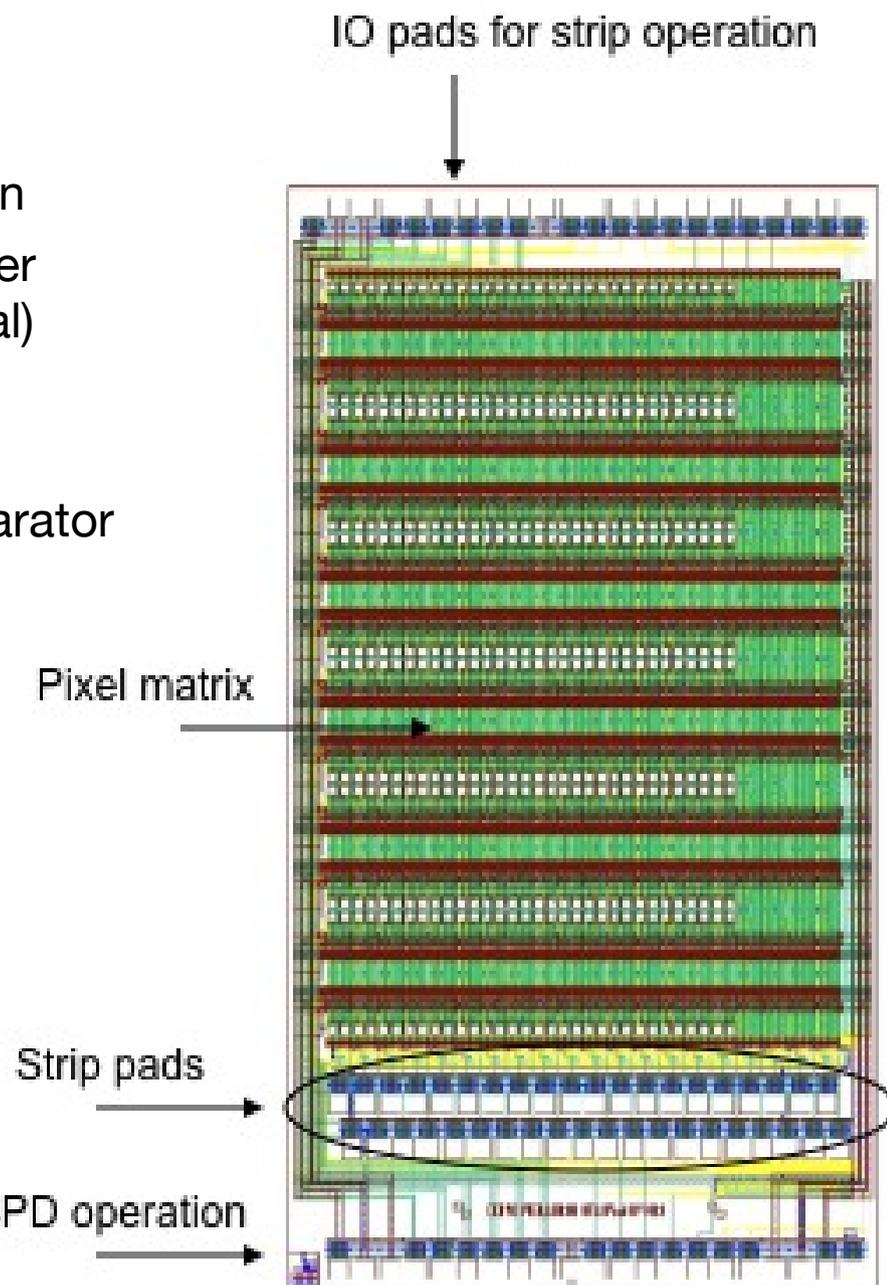
HV2FEI4

- ATLAS institutes submitted a combined active strip/pixel sensor
 - pixels match new ATLAS FE-I4 readout chip
 - capacitive coupling
 - bump-bonding possible
 - strips should be compatible with ATLAS ABCN and LHCb/Alibava Beetle
 - chip expected ~end of March



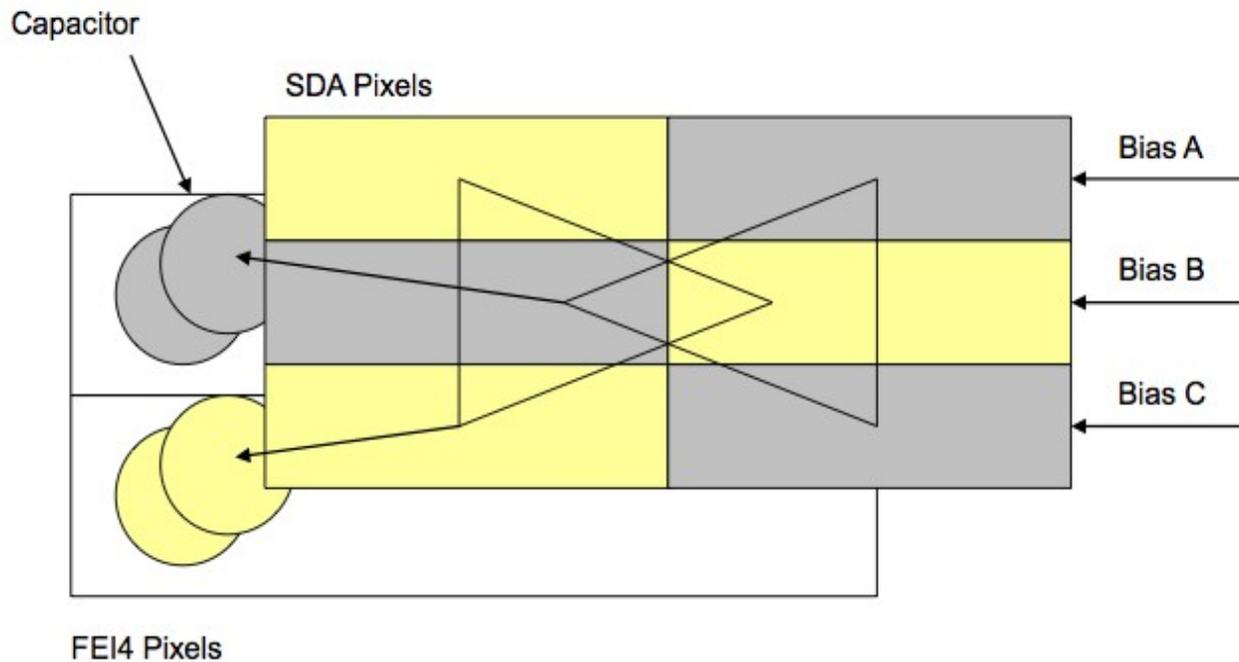
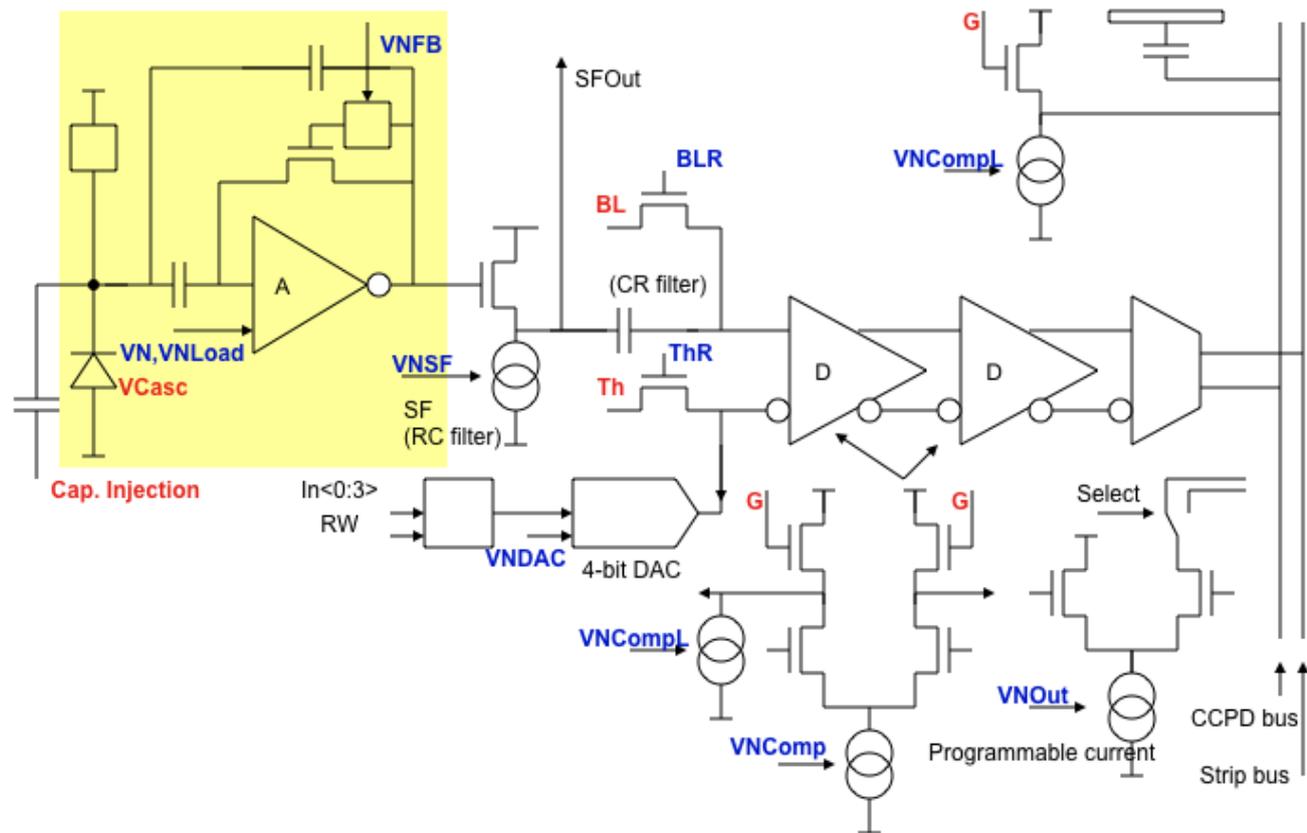
HV2FEI4

- Chip size: 2.2mm x 4.4mm
- Pixel matrix: 60x24 pixels
- Pixel size 33 μm x 125 μm
- 21 IO pads at the lower side for CCPD operation
- 40 strip-readout pads (100 μm pitch) at the lower side and 22 IO pads at the upper side for (virtual) strip operation
- On chip bias DACs
- Pixels contain charge sensitive amplifier, comparator and tune DAC
- Pads include:
 - Analog power (vdda 1.8V) and preamplifier supply 1.2V
 - Digital power (1.8V)
 - HV bias (-60V)
 - Threshold and base line voltages
 - Slow control for DACs
 - Test pulse (capacitive injection)



HV2FEI4

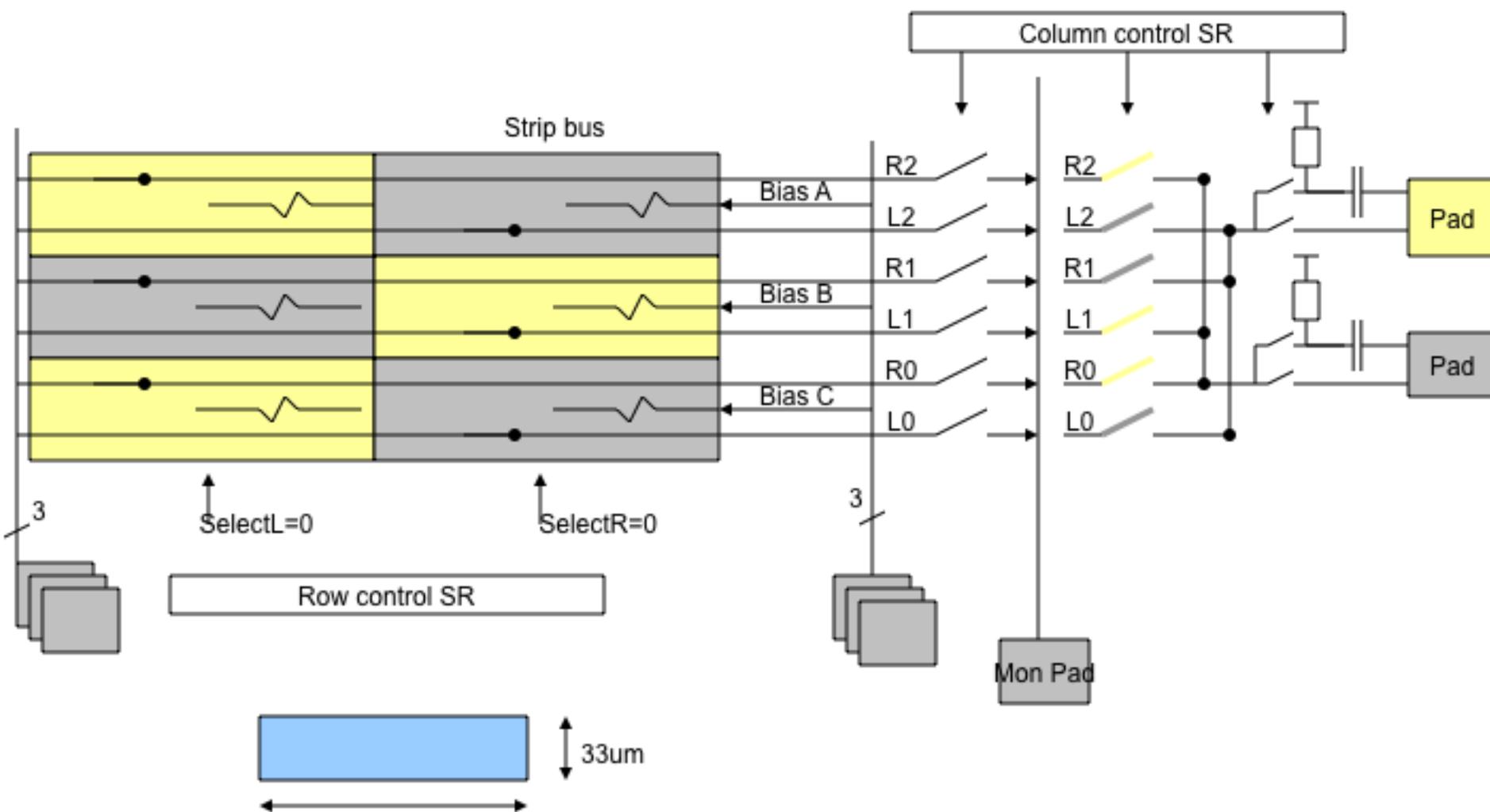
- Sub-pixel positions are encoded by 3-level pulses
 - additive: unique pulse heights for all pixel combinations
 - FE-I4's 4-bit ToT should be able to disentangle



HV2FEI4

- Strips readout: z-position encoding via resistor network
- r-phi encoding just “proof of concept” not yet really useful

Strip and Test-Operation



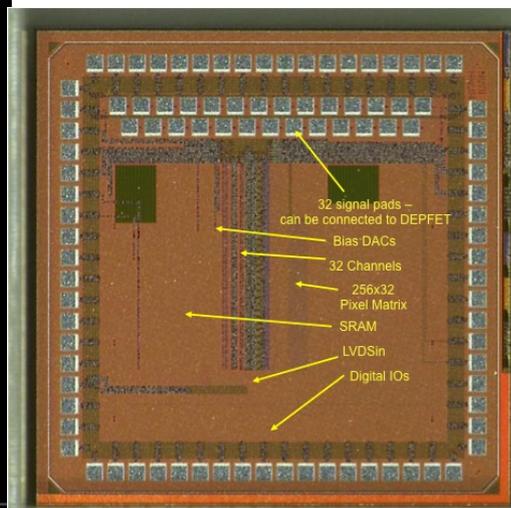
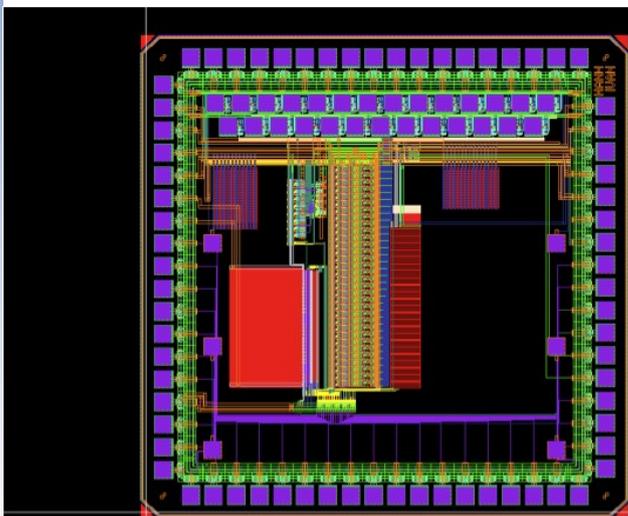
Outlook: back to MAPS?

- 3 aspects for further improvement:
 - reduce pixel sizes further – how far can one go?
 - reduce thickness of “module” to save radiation length
 - reduce cost for large scale usage of a system with pixel-resolution

- smaller pixel sizes
 - go to smaller feature size
 - digital part directly scales
 - analogue part at least partially
 - lower capacitance
 - even lower noise
 - less preamp-power (but of course more channels)
 - interconnect
 - no bump-bonding for pixels in the order of $10 \times 10 \mu\text{m}$ (maybe SLID)
 - capacitive coupling, but also here very dense
 - go to 3D interconnect? Maybe even 180nm HV-CMOS to 130nm CMOS?
 - go towards drift-based MAPS? In the end it's all a CMOS flavour...

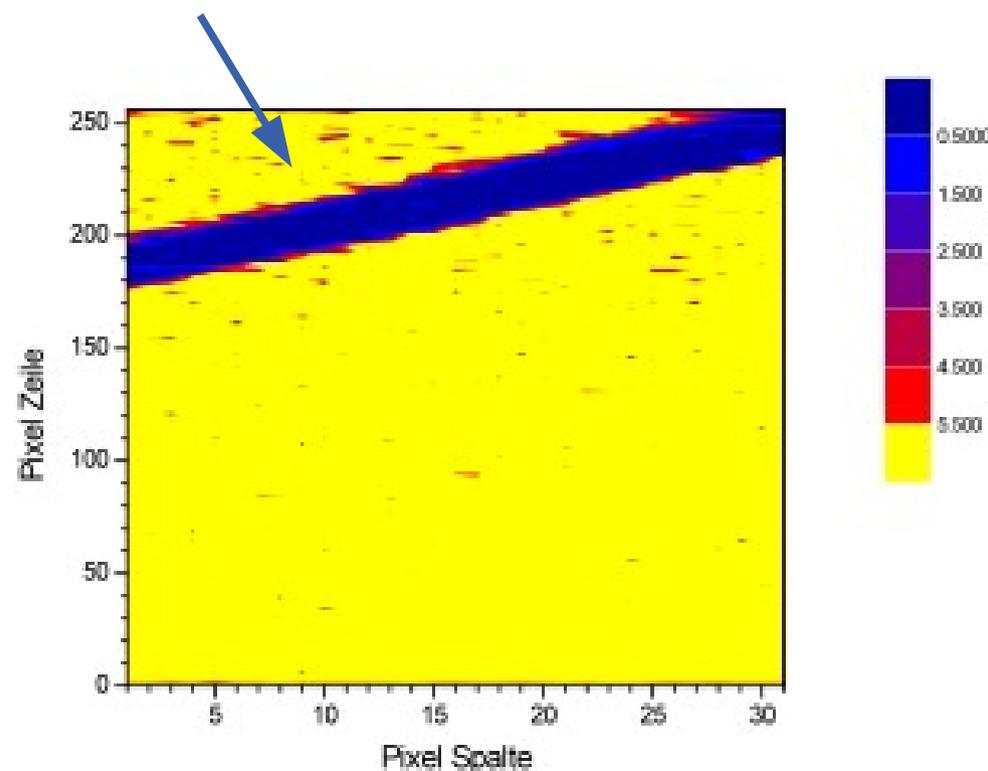
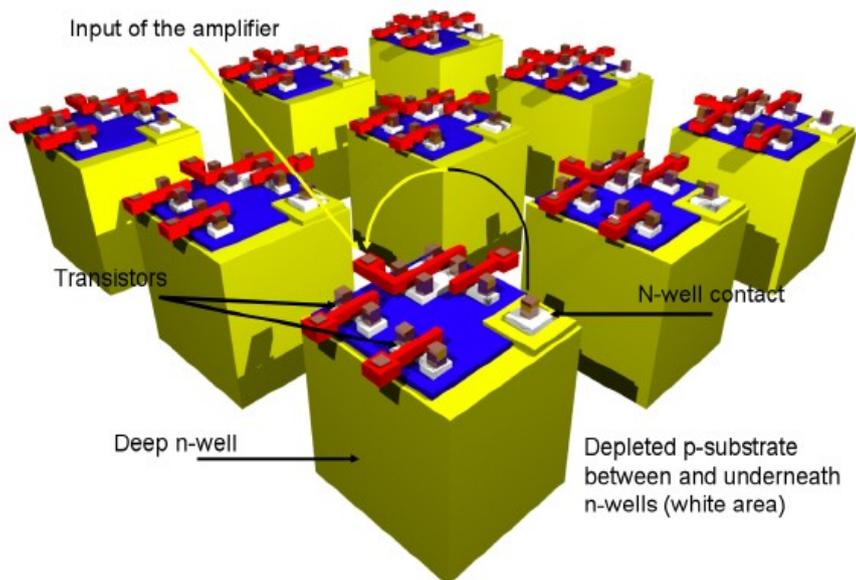
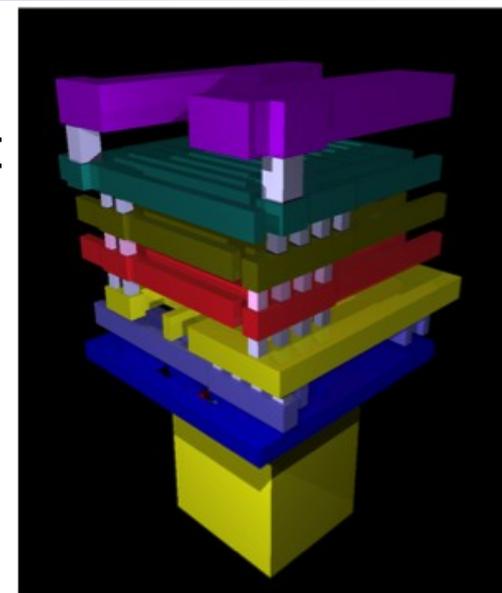
CMOS MAPS

- What feature size/pixel size should be used?
 - test chips in 350 and 180nm HV-CMOS had different pixel sizes and varying levels of intelligence, but were generally not fast enough/did not have time stamps with 40 MHz
 - FE-I4 in 130nm has a cell size of 50x250 μm → probably too large
 - 65nm aimed for by several chip developers within ATLAS
 - suitable as sensor/MAPS?
- 65nm process features
 - 20 $\text{Ohm}\cdot\text{cm}$ resistivity (!)
 - deep n-wells (not as deep as in HV processes, but might do)
 - work on 65nm chips has anyway started within ATLAS → synergy
 - first test chip containing tiny pixels (standard n-well) already done:



65nm test chip

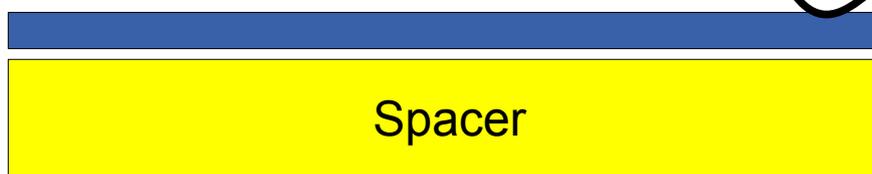
- Tiny pixels (2.5 μm pitch) with charge storage read-out sequentially
 - obviously not for HL-LHC, but 2.5 μm shows what is possible
 - 1 μm gaps between pixels, $\sim 1\text{V}$ bias voltage (!)
 - minimal charge sharing due to very shallow depletion zone: Na-22 clusters are 2-3 pixels
 - spatial resolution (\sim binary) of $2.5\mu\text{m}/\sqrt{12}=0.7\mu\text{m}$ (!!)
 - shadow of a 16 μm thick golden bond-wire



Realistically – what is desirable?

- resolution of tracks in dense jets would be highly welcome for various reasons
 - very thin depletion zone would help to avoid large clusters at high eta in innermost layers
 - realistic pixels sizes (area matters, not shape – can be square or rectangular)
 - $\sim 10 \times 10 \mu\text{m}$ with little intelligence, but with LHC-speed, sparse readout, ...
 - $\sim 20 \times 40 \mu\text{m}$ should be able to contain all features one could wish for
- track-trigger applications?
 - current ATLAS concepts work with short-strip layers without stereo-angle
 - 3 double-layers necessary due to fake-rate
 - improved resolution (in particular in z) would significantly reduce this
 - no loss of z-information for tracking purposes
 - better track resolution \rightarrow better spacer thickness/pT resolution ratio
 - MAPS-chips could already contain the combination logic

MAPS-1



MAPS-2



Conclusions

- HV-CMOS processes might yield radiation-hard, low-cost, improved-resolution, low-bias-voltage, low-mass sensors
- First test chips indicate rad-hardness up to at least $1e15$ n_{eq}/cm^2
 - general principles suggest rad-hardness up to full HL-LHC fluence
- Process can be used for
 - 'active' n-in-p sensors
 - drift-based MAPS chips (baseline for $\mu 3e$ -Experiment at PSI)
- First active sensor design submitted within ATLAS framework
 - capacitively coupled pixel sensors
 - “virtual” strip sensors
 - Irradiation and testbeam campaign planned for 2012
 - up to HL-LHC fluences
 - testbeam at CERN with Timepix telescope
- First test chip in standard 65nm CMOS process
 - pixels with $2.5 \mu m$ pitch, though no intelligence
 - only $\sim \mu m$ depletion, but S/N still good (low capacitance)
 - should try deep n-well allowing more bias voltage and some more realistic pixel size/intelligence